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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/618,850	07/15/2003	Yukio Tanaka	0756-7177	4342
31780 7	590 06/23/2006		EXAM	INER
ERIC ROBINSON			NHU, DAVID	
PMB 955 21010 SOUTHBANK ST.		ART UNIT	PAPER NUMBER	
POTOMAC FALLS, VA 20165			2818	
			DATE MAILED: 06/23/2000	5

Please find below and/or attached an Office communication concerning this application or proceeding.

		1/			
	Application No.	Applicant(s)			
	10/618,850	TANAKA ET AL.			
Office Action Summary	Examiner	Art Unit			
	David Nhu	2818			
The MAILING DATE of this communic Period for Reply	ation appears on the cover sheet w	ith the correspondence address			
A SHORTENED STATUTORY PERIOD FO WHICHEVER IS LONGER, FROM THE MA - Extensions of time may be available under the provisions of after SIX (6) MONTHS from the mailing date of this communing to the community of the provision of time may be available under the provisions of after SIX (6) MONTHS from the mailing date of this community of the NO period for reply is specified above, the maximum statute. Failure to reply within the set or extended period for reply with Any reply received by the Office later than three months after earned patent term adjustment. See 37 CFR 1.704(b).	ILING DATE OF THIS COMMUNI 37 CFR 1.136(a). In no event, however, may a inication. atory period will apply and will expire SIX (6) MON ill, by statute, cause the application to become Al	CATION. reply be timely filed NTHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).			
Status					
1)⊠ Responsive to communication(s) filed	on 11 October 2005				
,	b)⊠ This action is non-final.				
/ -	3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is				
closed in accordance with the practice	•	• •			
Disposition of Claims					
4) ⊠ Claim(s) <u>1-37</u> is/are pending in the ap 4a) Of the above claim(s) <u>1-7</u> is/are wi 5) ☐ Claim(s) is/are allowed. 6) ⊠ Claim(s) <u>8-37</u> is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restricti	ithdrawn from consideration.				
Application Papers					
9) The specification is objected to by the	Examiner.				
10) The drawing(s) filed on is/are:	a) accepted or b) objected to	by the Examiner.			
Applicant may not request that any objecti	on to the drawing(s) be held in abeya	nce. See 37 CFR 1.85(a).			
Replacement drawing sheet(s) including to the first three cath or declaration is objected to be seen as the first three catherings.	,				
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for a) All b) Some * c) None of: 1. Certified copies of the priority d 2. Certified copies of the priority d 3. Copies of the certified copies of application from the Internations * See the attached detailed Office action	ocuments have been received. ocuments have been received in A f the priority documents have been al Bureau (PCT Rule 17.2(a)).	0 9 1 4 3 8 , 4 3 2 Application No. <u>10/295,886</u> . I received in this National Stage			
Office has every					
Attachment(s) 1) Notice of References Cited (PTO-892)	∆ ☐ Interview	Summary (PTO-413)			
2) Notice of Draftsperson's Patent Drawing Review (PT	O-948) Paper No(s)/Mail Date			
Information Disclosure Statement(s) (PTO-1449 or P Paper No(s)/Mail Date		Informal Patent Application (PTO-152)			

DETAILED ACTIONS

Double Patenting

1. Claims 14-19, 26-31 of the application No. 10/618, 850 is rejected under the judicially created doctrine of obviousness-type double patenting over claims 1-28 of U. S. Patent No. 6,635,505 B2 since the claims, if allowed, would improperly extend the "right to exclude" already granted in the patent.

The subject matter claimed in the instant application and similar language recited in the patent claims obviously depict a similar method having either same steps and/or same materials, and such is also disclosed in both the patent and the instant application.

Specifications

2. There is no description of layer 1755 in figure 18A.

There is no description of layers 4204, 4025, 4027 in figure 25 B.

Drawings

3. There is no a gate insulating 1118, and a second impurity 114 in figure 12 A. Also there is no wiring 1107 in figure 12 B.

Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.
- 5. Claims 8-37 are rejected under 35 U.S.C. 102(e) as being anticipated Takemura et al

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(5,719,065).

Regarding claims 8, 14, 20, 26, 32, Takemura, (see figures 3F, 3H, 4B, 4C, 5A, 6A, 6C, 6F, 7A, 7C, 7F, col.7, lines 3-36, col. 8, lines 36-67, col. 9, lines 1-16, col. 9, lines 64-67, col. 10, lines 1-57), teaches a method of manufacturing a circuit comprising: forming first and second semiconductor layers 102, 103 over a substrate 101; forming a gate insulating film 104 over the first and second semiconductor layers; forming gate electrodes 105 over the first and second semiconductor layers with the gate insulating film interposed (see figure 6A); introducing a first impurity element 110 into portions of the first and second semiconductor layers so as to form first impurity regions; introducing a second impurity element 111into portions of the first and second semiconductor layers so as to form second impurity regions in contact with the first impurity regions; introducing a third impurity element 112 into portions of the first semiconductor layer so as to form third impurity regions in contact with the second impurity regions (see figures 3F, 6C,7C); forming wirings 116, 117, 503 so as to be in contact with the third impurity regions (see figures 3H, 4C, 5A, 6F, 7F); wherein an edge of the gate insulating 104' is aligned with a boundary between the second impurity regions 111 and the third impurity regions 112 (see figures 3F, 6C, 7C). Regarding claims 9, 15, 21, 27, 33, Takemura (see figures 3F, 6c, 7c), also teaches the third impurity regions is higher than the second impurity regions, and a concentration of the second impurity regions is higher than the first impurity regions (see col. 7, lines 3-36).

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Regarding claims 10, 22, 28, 34, Takemura, (see figures 3f, 6C, 7C), teaches the first, second, third impurity elements comprise phosphorus.

Regarding claims 11-13, 17-19, 23-25, 29-31, 35-37, (see figure 10), teaches a logic circuit; a display device (LCD); a computer...

Conclusion

- 5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Takemura'477, Yamaguchi'414, Ha'234, Yamazaki'735, Zhang'944, are cited as of interest.
- 6. A shortened statutory period for response to this action is set to expired 3 (three) months from the date of this letter. Failure to respond within the period for response will cause the application to become abandoned (see 710.02 (b)).
- 7. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

The fax phone number for the organization where this application or proceeding is assigned is (571)273-8300.

Information regarding the status of an application may be obtained from the patent application information retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR

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system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private

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PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

David Nhu

June 12, 2006